

# GCA Stepper

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## Facts

- The GCA stepper is a 5x stepper with environmental control.
  - Uses 5" x 5" x 0.09" soda lime photomasks.
  - Features on the photomask are reduced 5x down to the printed feature size.
  - Excellent tool for larger feature sizes.
  - Capable of features down to 1um in size
  - Capable of 0.35um pattern overlay
  - Field size of 20x20mm
  - Numerical aperture of 0.28
- It is configured for 100mm and 150mm wafers and uses the mercury g-line 436nm for exposure.
  - This system uses "pucks" to hold the wafers. Different pucks could be made for other substrate sizes.
- It has a larger depth of field and is useful for exposures over higher substrate topography - as can be found in MEMs devices

## Personnel

- Tool Engineer -
- Process Engineer - [Sean O'Brien](#)
- Process Engineer - [Patricia Meller](#)

## Manuals & Users

- [GCA Stepper Manual](#)
- [GCA Job Creation Manual](#)
- [GCA Certification Checklist](#)